

## A Potent Solvent for Dissolution of Metallic Copper

Naohisa Yanagihara,\* Masahiro Nakayama, and Hideo Tai

Department of Materials Science and Engineering, Teikyo University, 1-1 Toyosatodai, Utsunomiya 320-8551

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Metallic copper was found to dissolve in a mixture of ammonia and carbon tetrachloride under extremely mild conditions. The solubilized copper was determined to be in the form of an ammine complex of copper(II) chloride,  $[\text{Cu}(\text{NH}_3)_m]\text{Cl}_2 \cdot n\text{H}_2\text{O}$ .

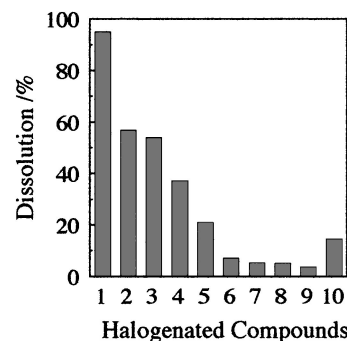
Mineral acids such as sulfuric acid, hydrochloric acid and nitric acid have traditionally been used to dissolve metals. In fact, they are still recognized as one of the most powerful and practical reagents for dissolving inorganic compounds, as well as metals. In contrast, only a few attempts have been made to dissolve metals in organic solvents. A recent report described the effectiveness of aprotic solvents such as dimethyl sulfoxide (DMSO) in dissolving metals.<sup>1-3</sup> Shortly thereafter it was shown that a variety of metals (e.g., Fe, Ni, Cu, Zn, Pd, Ag and Au) can be dissolved in a system consisting of a combination of a common organic solvent with an elemental halogen and a long-chain quaternary ammonium halide.<sup>4</sup> Perhaps more striking is the fact that a solvent system containing  $\text{Cl}_2$ ,  $\text{Me}_2\text{NHCl}$  and  $\text{MeCN}$  dissolves Au faster than *aqua regia*.<sup>5</sup>

It is widely known that copper readily dissolves in nitric acid and sulfuric acid in the presence of oxygen. Copper is also soluble in ammonium hydroxide, ammonium carbonate, or potassium cyanide in the presence of  $\text{O}_2$ . The redox potential of the Cu(I) and Cu(II) oxidation states are indicated by the following data:  $\text{Cu}^0 + \text{Cu}^{2+} \rightleftharpoons 2\text{Cu}^+$ ,  $E^0 = -0.37 \text{ V}$ .<sup>6</sup> The relative stabilities of the Cu(I) and Cu(II) ions in solution depend very strongly on the nature of the anions or other ligands present and varies considerably with the nature of the solvent. As part of our investigations on the chemistry of Cu(I) we have been preparing copper(I) complexes by the interaction of Cu(II) compounds with  $\text{Cu}^0$ . In the course of these investigations we made the striking observation that metallic copper can be dissolved in a solution of ammonia in the presence of carbon tetrachloride.

Bearing in mind the results of early studies that halogen and/or halogenated compounds play an important role in dissolving metals in organic solvents, we attempted to extend our preliminary observations to investigate in more detail the ability of solutions of ammonia mixed with halocarbons to dissolve metals.

Thus, we first examined the efficiency of solutions of ammonia mixed with several different halogenated compounds in dissolving metallic copper. To this end, 2.5 g (40 mmol) of copper powder was suspended in 50 mL of ammonia solution with stirring at 30 °C. To this suspension 20 mmol of halogenated compound was added. After 3 h of reaction a dark-blue solution was obtained. Upon filtering the unreacted solid, the content of copper in the supernatant was determined by EDTA titration.

As shown in Figure 1, among the 9 halogenated compounds used in this study, the solution of ammonia containing  $\text{CCl}_4$  exhibits the highest ability to dissolve metallic copper, although

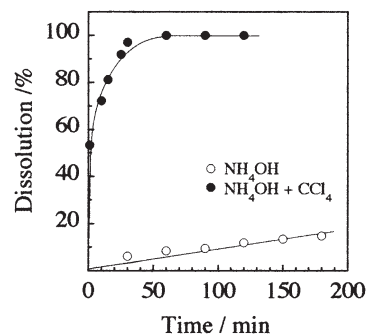


**Figure 1.** Dissolution of copper in ammonia solution containing various halogenated compound. Reaction conditions: Cu, 40 mmol; halogenated compound, 20 mmol;  $\text{NH}_4\text{OH}$ , 50 mL; 30 °C, 3 h. (1,  $\text{CCl}_4$ ; 2,  $\text{CHCl}_3$ ; 3,  $\text{CHBr}_2\text{CHBr}_2$ ; 4,  $\text{CH}_2\text{Br}_2$ ; 5,  $\text{CH}_3\text{CCl}_3$ ; 6,  $\text{CHCl}_2\text{CHCl}_2$ ; 7,  $\text{CH}_2\text{ClCHCl}_2$ ; 8,  $\text{CCl}_2\text{CCl}_2$ ; 9,  $\text{CH}_2\text{ClCH}_2\text{Cl}$ ; 10,  $\text{NH}_4\text{OH}$ ).

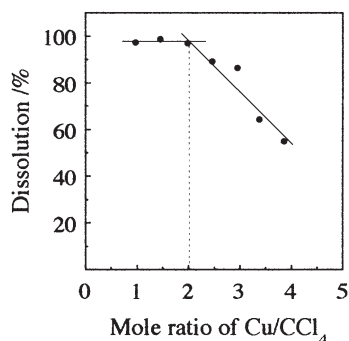
other combined ammoniacal solution (i.e.,  $\text{NH}_4\text{OH}-\text{CHCl}_3$  and  $\text{NH}_4\text{OH}-\text{Br}_2\text{CHCHBr}_2$ ) showed moderate dissolution power toward  $\text{Cu}^0$ .

We then concentrated our efforts to investigate some of the details of the dissolution reaction of  $\text{Cu}^0$  in the solvent system consisting of  $\text{NH}_4\text{OH}-\text{CCl}_4$ . Figure 2 illustrates the efficiency of  $\text{CCl}_4$  on the dissolution of metallic copper. The dissolution of  $\text{Cu}^0$  in the  $\text{NH}_4\text{OH}-\text{CCl}_4$  system reached an almost quantitative yield within 1 h, whereas that in the system without  $\text{CCl}_4$  was less than 10% at the same time. Furthermore, it is noteworthy that the dissolution of  $\text{Cu}^0$  in  $\text{NH}_4\text{OH}-\text{CCl}_4$  proceeds 150 times faster than that in  $\text{NH}_4\text{OH}$  alone, if the initial slopes of each curve in Figure 2 are taken as a measure of the relative rate constants.

In order to elucidate the stoichiometry of this reaction, the effect of the mole ratio of  $\text{Cu}^0/\text{CCl}_4$  on the dissolution of  $\text{Cu}^0$  was examined. It is apparent from Figure 3 that the reaction pro-



**Figure 2.** Effect of addition of  $\text{CCl}_4$  on the dissolution of copper in ammonia solution at 30 °C; Cu, 80 mmol;  $\text{CCl}_4$ , 40 mmol;  $\text{NH}_4\text{OH}$ , 100 mL.



**Figure 3.** Variation of the dissolution of copper with the mole ratio of Cu/CCl<sub>4</sub>; CCl<sub>4</sub>, 20 mmol; NH<sub>4</sub>OH, 50 mL; 30 °C, 3 h.

ceeds with a stoichiometry of Cu<sup>0</sup>:CCl<sub>4</sub> = 2:1. In an attempt to understand the reaction mechanism, the reaction products and volatile components were analyzed. The former were analyzed by concentrating the resultant ammoniacal solution mixture, and examining the solid by titration,<sup>7</sup> IR and TG-DTA.<sup>8</sup> Based on these analyses, the product was determined to be an amine complex of copper(II) chloride, [Cu(NH<sub>3</sub>)<sub>m</sub>]Cl<sub>2</sub>·nH<sub>2</sub>O. The volatile component, which was trapped during the reaction, was identified to be CH<sub>2</sub>Cl<sub>2</sub> by <sup>1</sup>H-NMR.<sup>9</sup>

On the study of dissolution of metallic copper in a dimethyl sulfoxide (DMSO)-CCl<sub>4</sub> system,<sup>2</sup> Tezuka, et. al. proposed the generation of a dichlorocarbene intermediate via an interaction between Cu<sup>0</sup> and CCl<sub>4</sub>. Since we found CH<sub>2</sub>Cl<sub>2</sub> in our NH<sub>4</sub>OH-CCl<sub>4</sub> system, it seems reasonable to assume that a dichlorocarbene could also be formed in our reaction system. Thus, the following over-all reaction might be proposed, although the reaction mechanism is not clear at this time and attempts to confirm the generation of CO failed.



The dissolution ability of the NH<sub>4</sub>OH-CCl<sub>4</sub> system for typical metals such as Zn, Ag, Sn, Pb, and Fe was also examined with conditions similar to those used to dissolve Cu. The solvent system was able to dissolve Zn but the efficiency was ca. 60%, relative to Cu. The dissolution of both Ag and Sn were less than 0.5%. However, it was found that Pb and Fe were not dissolved in NH<sub>4</sub>OH-CCl<sub>4</sub> solvent. Although the reason why there is a difference in the dissolution of metals by NH<sub>4</sub>OH-CCl<sub>4</sub> system is not clear at the present time, ease of the decomposition of CCl<sub>4</sub> as well as the formation of dichloro-

carbene by metals, and that of the ammine complex formation might play an important role.

In summary, it has been found that some halogenated compounds can be decomposed by metallic copper in NH<sub>4</sub>OH. Furthermore, it was found that a unique solvent system consisting of a mixture of NH<sub>4</sub>OH and CCl<sub>4</sub> can quantitatively dissolve metallic copper at ambient temperature. Since the solvent system has an excellent efficiency and a good selectivity toward metallic copper, this method might be applicable as a promising process for selective leaching of metallic copper from waste printed wiring boards. Indeed, in additional experiments, it was found that the dissolution ability of NH<sub>4</sub>OH-CCl<sub>4</sub> system in the leaching of copper from waste printed circuits at ambient temperature is almost comparable to that in mineral acid such as HNO<sub>3</sub>, when the concentration of acid is the same as that of NH<sub>4</sub>OH.

Further studies to reveal detail mechanism of the dissolution of metallic copper in NH<sub>4</sub>OH-CCl<sub>4</sub> system are now in progress.

#### References and Notes

- 1 M. D. Benari, G. T. Hefter, and A. J. Parker, *Hydrometallurgy*, **10**, 367 (1983).
- 2 Y. Tezuka, M. Miya, A. Hashimoto, and K. Imai, *J. Chem. Soc., Chem. Commun.*, **1987**, 1642.
- 3 J. B. Gill, D. C. Goodall, and W. D. Harrison, *J. Chem. Soc., Dalton Trans.*, **1987**, 2997.
- 4 Y. Nakao, *J. Chem. Res.*, **1991**, 228.
- 5 Y. Nakao, *J. Chem. Soc., Chem. Commun.*, **1992**, 426.
- 6 F. A. Cotton and G. Wilkinson, in "Advanced Inorganic Chemistry," 5th ed., John Wiley & Sons, New York (1988), p. 757.
- 7 Since the composition of residue was varied with drying conditions, the final solution was concentrated and dried in vacuo at 100 °C. The contents of copper ion and chloride ion were determined by EDTA titration and Volhard method, respectively. Found: Cu, 33.6; Cl, 37.2%.
- 8 The final solution was concentrated and dried gently at ambient temperature. IR(KBr)/cm<sup>-1</sup>: 3492 for νOH; 3314 for ν<sub>as</sub>NH<sub>3</sub>; 3184 for ν<sub>s</sub>(NH<sub>3</sub>). Observed and calculated weight loss percentage in parenthesis, and possible assignment of eliminant, assuming that the residue is [Cu(NH<sub>3</sub>)<sub>4</sub>]Cl<sub>2</sub>·4H<sub>2</sub>O: 17.4 (18.9)% at ca. 240 °C for 3H<sub>2</sub>O; 20.3 (22.9)% at 240–270 °C for (3H<sub>2</sub>O + NH<sub>3</sub>); 15.9 (16.4)% at 390–480 °C for 3NH<sub>3</sub>.
- 9 <sup>1</sup>H-NMR(400 MHz, CDCl<sub>3</sub>, TMS): δ 5.30 (s).